	Type	L #	Hits	Search Text	DBs
1	BRS	L1	1	(depoless adj3 etch\$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
2	BRS	L2	1	(depoless adj3 etch\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
3	BRS :	L3	34313	(first adj10 plasma)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
4	BRS	L4	28850	(second\$2 adj10 plasma)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
5	; BRS ·	L5	10256	13 with 14	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
6	BRS	L6	1	(dry adj3 clean\$4) with (dummy) adj10 (wafer or substrate or silicon or semiconductor)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
7	BRS	L7	2	15 same 16	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
8	BRS	L8 .	16	15 and 16	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
	BRS ·		7	("5221425" "5423941" "5522966" "5647953" "5728602" "5746928" "5810937").PN.	US-PGPUB; USPAT; USOCR
10	BRS	L10	26	("6090718").URPN.	USPAT

	Type	L#	Hits	Search Text	DBs
11	BRS	L11	11 / 3811/	, ,	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
12	BRS	L12	132268	(first or initial\$3) adj10	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
13	BRS	L13	110328	(second\$3) adj10 (etch\$4 or plasma)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
14	BRS	L14	55972	112 same 113	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
15	BRS	L15	662	(dry adj3 clean\$4 or condition\$4) with (dummy) adj10 (wafer or substrate or silicon or semiconductor)	
16	BRS	L16	58	114 and 115	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Type	L	#	Hits	Search Text	DBs
1	BRS	L1		1114478	stripping or stripped or stripper) with (contaminant or	USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
2	BRS	L2		16312	or treating or treated) with	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
3	BRS	L3		25529	"CHF" or "SF") adj3 gas) with (oxygen or "O2" or "O.sub.2" or	
4	BRS	L4		26198	I"('HE'" Or "SE") adak das 1 with	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Туре	L#	Hits	Search Text	DBs
5	BRS	L5	298	12 same 11 same (dummy or dummies)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
6	BRS	L6	43	15 and 14	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
7	BRS	L7	423098	("134"/\$ or "216"/\$ or "156"/\$	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
8	BRS	L8	34	sakima-h\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
9	BRS	L9 ·	1	16 and 18	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
10	BRS	L10	0	("2004/0099634").URPN.	USPAT
11	BRS	L11	52195	(clean or cleaning or cleaned or cleaner or cleanse or cleansing or cleansed or treat or treating or treated or process\$4) with (plasma or etch\$3 or CVD or deposition or chemical adj vapor adj deposition) adj10 (chamber or reactor or vessel or container)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
12	BRS	L12	393	12 same 111 same (dummy or dummies)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
13	BRS	L14	45	113 and 17	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Туре	L #	Hits	Search Text	DBs
14	BRS	L13	54	 112 and 14	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
15	BRS	L15	1		ł I
16	BRS	L16	141	12 and 111 and 14 and (dummy or dummies)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
17	BRS	L17 _.	1	Į ·	
18	BRS	L18	6484	ll and (dummy or dummies)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
19	BRS	L19	1411	lll and (dummy or dummies)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
20	BRS	L20	5		
21	BRS	L21	105	ll 16 and (MHz)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
22	BRS	L22	2 ·		US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Type	L #	Hits	Search Text	DBs
23	BRS	L23	77	l16 and ("13.56")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
24	BRS .	L24	0	ILIO ANG ("IS.SO" AGIS (MHZ OR	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
25	BRS	L25	76		US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
26	BRS	L26	26		US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB